

Tutorial “Fundamentals and Trends in Plasma Surface Processing”

in Connection with 9th International Conference on Plasma Surface Engineering (PSE 2004)

Time Saturday, September 11

13:30 – 14:45 **FUNDAMENTALS OF PLASMAS FOR THIN FILM DEPOSITION**
H. Kersten
Institute of Low-Temperature Plasma Physics, Greifswald (Germany)

14:45 – 16:00 **PLASMA-SURFACE INTERACTION AND ION BOMBARDMENT**
W. Möller
Forschungszentrum Rossendorf, Dresden (Germany)

16:00 – 16:30 Coffee Break

16:30 – 17:45 **FUNDAMENTALS OF REACTIVE SPUTTERING**
S. Berg
Ångstrom Laboratory, University of Uppsala (Sweden)

17:45 – 19:00 **HIGH-POWER PULSED MAGNETRON SPUTTERING**
U. Helmersson
Thin Film Group, University of Linköping (Sweden)

19:30 Dinner and Social Get-Together

Sunday, September 12

8:45 – 10:00 **ADVANCED PLASMA DIAGNOSTICS FOR THIN FILM DEPOSITION**
M.C.M. van de Sanden
Dept. of Applied Physics, Eindhoven University of Technology (The Netherlands)

10:00 – 11:15 **PROCESS CONTROL FOR LARGE AREA MAGNETRON SPUTTERING**
J. Strümpfel
Von Ardenne Anlagentechnik GmbH, Dresden (Germany)

11:15 – 12:30 **THIN FILM STRESS AND TEXTURE CONTROL**
J. Bøttiger
Institute of Physics and Astronomy, University of Århus (Denmark)

12:30 – 14:00 Lunch

14:00 – 15:15 **CARBON-BASED HARD COATINGS**
B. Schultrich
Fraunhofer Institute for Material and Beam Technology, Dresden (Germany))

15:15 – 16:30 **PLASMA TREATMENT OF POLYMERS**
Chr. Oehr
Fraunhofer Institute of Interfacial Engineering and Biotechnology, Stuttgart (Germany)

Please note that an additional registration for the tutorial is necessary. An early registration is recommended because the number of participants is limited.

The registration form is also available at www.akplasma.org/pse.php3.